

01-719

IN THE SPECIFICATION

Please replace the eighth and ninth paragraphs on page 5 of the specification with the following:

Fig. 7-8 is a cross sectional view of the mask substrate containing patterned layers according to a third embodiment of the invention, and

Fig. 8-9 is a schematic representation of a process using a phase shift mask made according to the invention to form structures in an integrated circuit.